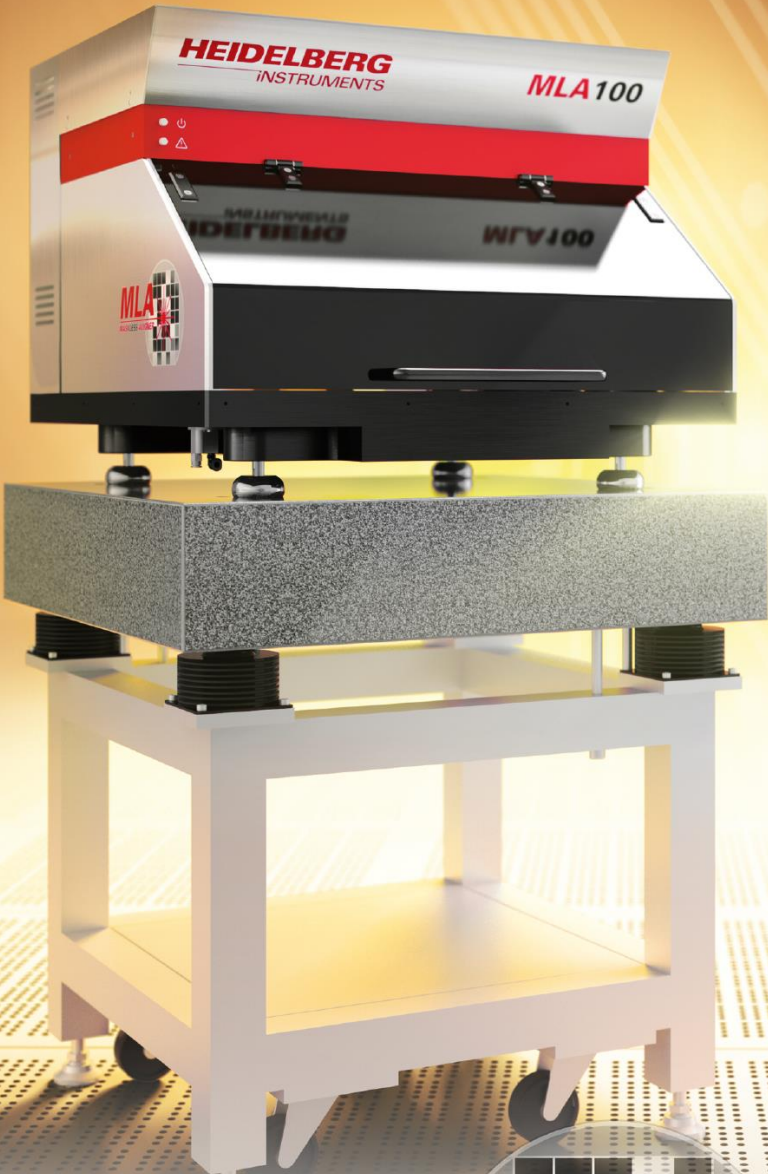


MLA100

HEIDELBERG
INSTRUMENTS



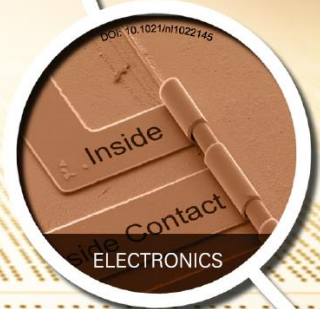
MEMS



SENSORS

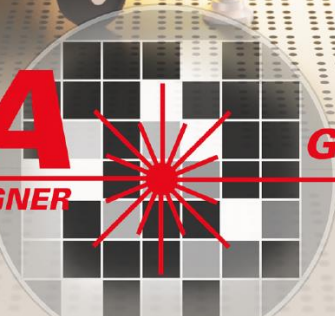


GRAY SCALE

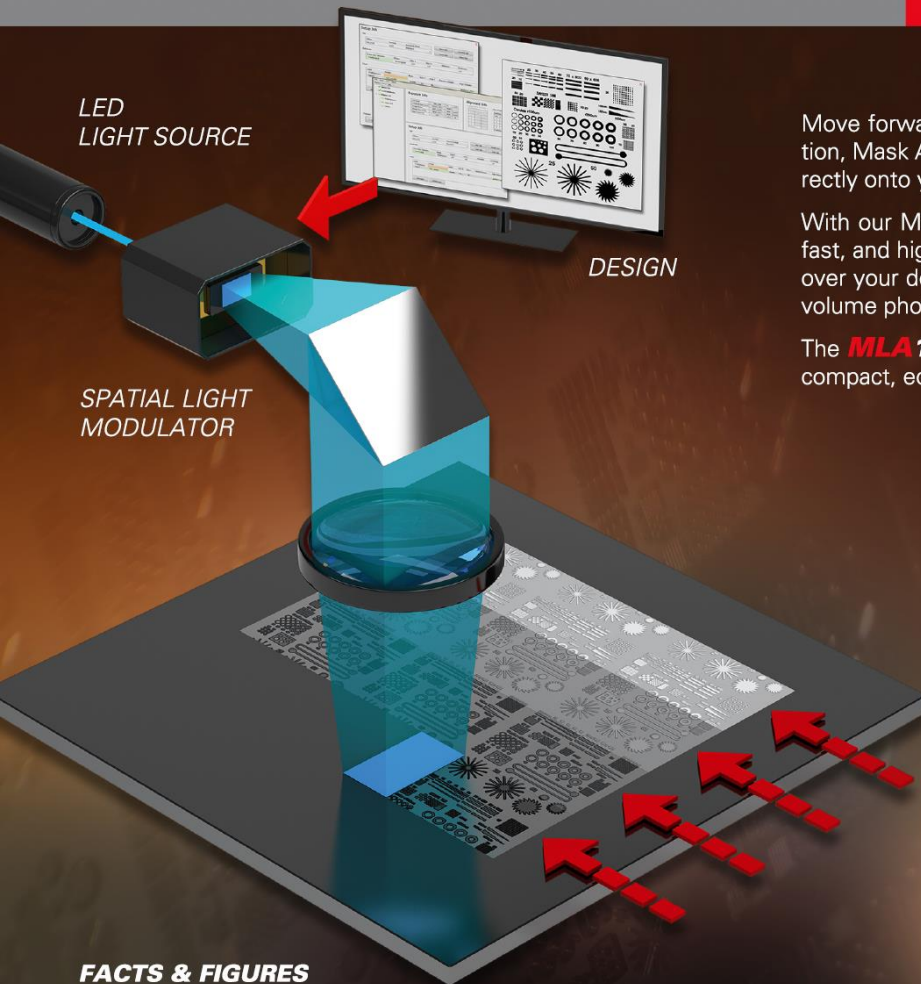


ELECTRONICS

MLA
MASKLESS ALIGNER



GO MASKLESS
ACHIEVE MORE



LED
LIGHT SOURCE

DESIGN

SPATIAL LIGHT
MODULATOR

Move forward - from the traditional (CAD layout, photomask fabrication, Mask Aligner) into the future: create the design and expose it directly onto your wafer – no photomask necessary!

With our Maskless Aligners (MLA), this becomes a straightforward, fast, and highly precise procedure, giving you every control you need over your design and patterning process, in particular in low to mid-volume photolithography applications like prototyping and R&D.

The **MLA100** is the tabletop maskless aligner in our MLA series – compact, economical, and versatile, with a focus on the ease of use.

FLEXIBILITY

Put your designs and patterns into practice any time you need them; implement small changes without delay; experiment without restrictions – and generally eliminate the cost, time, and inconvenience associated with photomasks!

MLA
MASKLESS ALIGNER

FACTS & FIGURES

WRITING PERFORMANCE

Minimum feature size	1 μm
Linewidth variation [3 σ]	200 nm
2nd layer alignment [3 σ]	1 μm
Maximum exposure area	125 x 125 mm ²
Exposure time	50 min for 50 x 50 mm ²
(at maximum write speed)	200 min for 100 x 100 mm ²

SYSTEM SPECIFICATIONS

Light source	LED: 10 W at 390 nm or LED: 10 W at 365 nm
Substrate sizes	Variable: 5 x 5 mm ² up to 6" x 6"
Size detection	Automatic
Alignment mode	Front side alignment
Software	Intuitive, with on-screen guidance; supports all standard input formats (dxf, gdsii, cif, gerber); includes CAD software for design creation
System dimensions	W: 630 mm (25"); D: 800 mm (31.5"); H: 530 mm (21")
Good to know	Non-contact exposure; compatible with g-, h-, and i-line resists; automatic labeling and serialization; overview camera for rapid positioning and easy alignment on substrate; real-time autofocus system; Draw Mode for CAD-less exposures; Gray Scale Mode: 128 gray levels

SPEED

From design to finished structure in minutes: For example, it will take you 8 minutes only to expose a 20 x 20 mm² area, irrespective of the number of structures or the fill factor. In addition, system setup, loading, and alignment require just minutes to accomplish.



GO MASKLESS
ACHIEVE MORE

Specifications depend on individual process conditions and can vary according to equipment configurations. Design and specifications are subject to change without prior notice.

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